Simple Formation of C_{60} and C_{60}-Ferrocene Conjugated Monolayers Anchored onto Silicon Oxide with Five Carboxylic Acids and Their Transistor Applications

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C_{60} and C_{60}-ferrocene conjugated molecule bearing five carboxylic acids successfully anchor onto a silicon oxide surface as a monolayer through a simple method of simply dipping an amino-terminated surface into the solution of the C_{60} derivatives. The monolayer structure was characterized by UV−vis spectroscopy, X-ray reflectivity, X-ray photoelectron spectroscopy, and IR spectroscopy to reveal that the molecules are standing presenting its C_{60} spherical face at the surface. The electronic effect of the C_{60} monolayer and the ferrocene-functionalized C_{60} monolayer in OFET devices was investigated. When an n-type OFET was fabricated on the ferrocene functionalized monolayer, we see an enhancement in the mobility. When a p-type OFET was made the ferrocene-functionalized C_{60} monolayer showed a lowering of the carrier mobility.

Introduction

In this study, we investigate self-assembled monolayers (SAMs) of anisotropically functionalized C_{60} molecules, and we explore the feasibility of these SAMs as electrically active materials in field-effect transistors (FETs). C_{60}, also known as buckminsterfullerene, is an attractive material for electronic applications, such as photovoltaics and active materials in field-effect transistors (FETs). C_{60}, also known as buckminsterfullerene, is an attractive material for electronic applications, such as photovoltaics and active materials in field-effect transistors (FETs). C_{60}, also known as buckminsterfullerene, is an attractive material for electronic applications, such as photovoltaics and active materials in field-effect transistors (FETs).

There have been many studies of a monolayer of C_{60} derivatives on gold, ITO, or other substrates. However, compared to the monolayer on gold, there are only a few reports for the formation of fullerene monolayers on silicon oxide surfaces that are important for electronic device applications especially for organic FETs. Moreover, all of these prior studies involve covalent functionalization on silicon oxide surfaces. Some of them make a reaction of C_{60} itself with a nitrogen functional group on the surface, as suggested by its high electron mobilities. Of particular interests are the SAMs of C_{60} showing unique properties and potential for advanced electronic applications.

The C60 derivatives 1 and 2 were synthesized according to the reported procedure. Quartz flats for UV-vis spectroscopy were purchased from NSG Precision Cells Inc. Silicon wafers for AFM, X-ray reflectivity, X-ray photoelectron spectroscopy, ATR-IR, and FET fabrication were obtained from Process Specialties Inc. High purity C60 (>99.9%, sublimed) from a separate sample without C60 and then fixed in the subsequent fit.11 XPS experiments were performed with a Kratos AXIS-Ultra Spectrometer equipped with a monochromatic Al source operated at 255 W. The pass energy was set to 160 eV for survey spectrum and 20 eV for high resolution scan of N1s. IR spectroscopy was performed by using a N2-purged Nicolet IR spectrometer with a mercury cadmium tellurium (MCT) detector. Spectra were obtained by using a GATR (Harrick Inc.) total reflectance accessory equipped with a hemispherical germanium crystal.

**FET Device Fabrication.** Bottom-contact geometry was used in all the transistor devices. A highly n-type doped (< 0.005 Ωcm) Si wafer with a 300 nm thermally grown silicon oxide surface was used for electrical measurements. The wafer was cleaned with 70:30 = H2SO4/30% H2O2 (Caution: This is called a piranha solution and is an extremely dangerous oxidizing agent. The solution should be handled with care using appropriate shielding.) for 1 h at 100 °C. Then, source and drain electrodes (5 nm Cr followed by 30 nm Au) were vacuum-deposited through a shadow mask. The resulting channel was (W, L) = (115 μm, 10 μm) for C60 transistors and (W, L) = (2 mm, 85 μm) for HBC transistors. The monolayer of 1 and 2 were formed according to the procedure described earlier. C60 transistors were then fabricated by thermal evaporation of 50 nm C60 on to the substrate at 1.5–1.7 Å/s at < 10^-6 Torr. HBC transistors were fabricated by spin coating 1 mg/mL solution of 3 in CHCl3 (or CH2Cl2) at 1200 rpm for 20 s. The transistor characterization was carried out at room temperature, in Ar atmosphere (C60 transistors) or in an ambient atmosphere (HBC transistors) using an Agilent 4155C semiconductor characterization system and a Karl Suss (PM5) manual probe station. The mobility was calculated according to ref 12.

**Results and Discussions**

A monolayer of 1 was formed on an amine-modified silicon oxide surface. First, a monolayer of 3-aminopropyltriethoxysilane (APTES) was formed on a silicon oxide surface;13 then, the substrate was immersed into a 0.1 mM solution of N2 gas, the samples were immersed in a 2 v/v % solution of 3-aminopropyltriethoxysilane (APTES) in ethanol for 25 min at room temperature. Post bake at 120 °C for 5 min gave the monolayer of APTES. The APTES covered samples were then immersed in 0.1 mM solution of 1 (or 2) in THF for 24 h (30 min for 2) at room temperature. After the monolayer assembly, the samples were soaked in clean THF for 30 min at room temperature for washing out the unbound molecules.

**Surface Characterization.** UV-vis spectroscopy was performed with a single-beam Agilent 8453 spectrometer with a modified sample holder. The monolayer was formed on ultrathin quartz flats to reduce background contributions. X-ray reflectivity measurements were performed at the National Synchrotron Light Source on beamline X22A using an X-ray beam of 32 KeV and 15 μm vertical and 1 mm horizontal beam size. The X-ray reflectivity data were fitted using a box-based model having discrete layers corresponding to the Si substrate, native oxide layer, the APTES layer, and C60. The parameters for fitting have been adjusted with a Marquardt-Levenberg least-squares routine. Since the scattering length density (SLD) contrast between the APTES layer and the C60 material is low, to avoid the interdependence of the fitting parameters during the fitting procedure, the parameters corresponding to the APTES layer have been obtained from a separate sample without C60 and then fixed in the subsequent fit. **11 XPS experiments were performed with a Kratos AXIS-Ultra Spectrometer equipped with a monochromatic Al source operated at 255 W. The pass energy was set to 160 eV for survey spectrum and 20 eV for high resolution scan of N1s. IR spectroscopy was performed by using a N2-purged Nicolet IR spectrometer with a mercury cadmium tellurium (MCT) detector. Spectra were obtained by using a GATR (Harrick Inc.) total reflectance accessory equipped with a hemispherical germanium crystal.**

**Experimental Section**

**Materials.** The C60 derivatives 1 and 27,10 and contorted hexabenzocoronene (HBC) derivative 3 (Figure 1)9 were synthesized according to the reported procedure. The C60 derivatives 1 and 2 were synthesized according to the reported procedure. Quartz flats for UV–vis spectroscopy were purchased from NSG Precision Cells Inc. Silicon wafers for AFM, X-ray reflectivity, X-ray photoelectron spectroscopy, ATR-IR, and FET fabrication were obtained from Process Specialties Inc. High purity C60 (>99.9%, sublimed) was purchased from Backy USA.

**Monolayer Formation.** Silicon oxide surfaces were cleaned by soaking them into CH3Cl2 at room temperature for 15 min followed by 20 min in a 1:1:5 = NH4OH:30% H2O2:DI H2O at 70 °C. Immediately after rinsing in DI H2O and drying in a steam of N2 gas, the samples were immersed in a 2 v/v % solution of 3-aminopropyltriethoxysilane (APTES) in ethanol for 25 min at room temperature. Post bake at 120 °C for 5 min gave the monolayer of APTES. The APTES covered samples were then immersed in 0.1 mM solution of 1 (or 2) in THF for 24 h (30 min for 2) at room temperature. After the monolayer assembly, the samples were soaked in clean THF for 30 min at room temperature for washing out the unbound molecules.

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**Results and Discussions**

A monolayer of 1 was formed on an amine-modified silicon oxide surface. First, a monolayer of 3-aminopropyltriethoxysilane (APTES) was formed on a silicon oxide surface;13 then, the substrate was immersed into a 0.1 mM
solution of 1 in THF at room temperature for 24 h without any coupling reagent. The coverage on the surface was calculated to be 0.42 molecules/nm$^2$ from the absorption cross section ($5.3 \times 10^{-16}$ cm$^2$/molecules in THF solution. See Supporting Information). This value is in good agreement with the calculated value for tightly packed molecules standing upright to the surface (0.45 molecules/nm$^2$, Figure 2). A monolayer of 2 (coverage = 0.50 molecules/nm$^2$) was obtained in the same way except that the substrate was immersed in the solution of 2 for 30 min; this was to avoid the formation of multilayer of 2. AFM images showed that the monolayers were uniform (Figure 3 and Supporting Information Figures S-7 and S-8). Without using an amine-modified surface, the immersion gave only islands of the molecules rather than uniform layers. Structural analysis of the monolayer was performed using synchrotron X-ray reflectivity, XPS, IR, and UV−vis spectroscopy. From synchrotron X-ray reflectivity, information about the thickness, electron density distribution, and roughness of the monolayers was obtained. Figure 4a shows the reflectivity data corresponding to the layer of 1 together with the fit. The fit was calculated based on a box model having discrete layers corresponding to the Si substrate, native oxide, the APTES layer and the C$_{60}$ derivative 1. The parameters corresponding to the APTES layer were obtained from a separate sample lacking 1 and were then fixed in the subsequent fit. The corresponding scattering length density (SLD) as a function of the film depth is shown in Figure 4b. This analysis gave thicknesses of 10.9 ± 0.2 Å for 1 and 12.9 ± 0.2 Å for 2 (Supporting Information Table S-1). These numbers agree quite well with the size of the molecules and indicate the formation of a single monolayer. Surface roughness of the monolayer is 5.0 ± 0.2 Å for 1 and 4.9 ± 0.3 Å for 2, and these values are in good agreement with the result of AFM (Supporting Information Figure S-5–8).

The XPS spectrum shows that hydrogen bonding is involved in the monolayer formation. Figure 5a is an XPS

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spectrum of N1s (escape angle 0°) of an APTES monolayer in the absence of \( \mathbf{1} \); there are two peaks that can be assigned to \(-\text{NH}_2 (400.1 \text{ eV})\) and \(-\text{NH}_3^+ (401.9 \text{ eV})\) in a ratio of 81:19. This is consistent with the previous report.\(^{13d}\) After the monolayer of \( \mathbf{1} \) is formed, the ratio of \(-\text{NH}_2\) and \(-\text{NH}_3^+\) peaks became 67:33 (Figure 5b), which implies the formation of a salt between the compound \( \mathbf{1} \) and APTES monolayer. XPS spectrum of the monolayer of \( \mathbf{2} \) gave essentially the same result (Supporting Information Figure S-11). In addition, the ratio of Fe and C (Fe/C = 1.3 \text{ 
} 10^{-2}) decreased when the spectrum was taken with the escape angle of 75° (Fe/C = 7.4 \text{ 
} 10^{-3}) which in turn suggest the upright orientation of the compound \( \mathbf{2} \) on the surface.

Infrared spectroscopy yielded further chemical information about the interface of the monolayer of \( \mathbf{1} \) and APTES. The C=O stretch of pure \( \mathbf{1} \) (1701 cm\(^{-1}\), Figure 6a) disappeared in the spectrum of the monolayer (Figure 6b). Instead, asymmetric and symmetric stretching modes of carboxylate CO\(_2^-\) (1608 and 1396 cm\(^{-1}\), respectively) became predominant, which suggests that \( \mathbf{1} \) is attached to the amine surface through hydrogen bonding. The differential spectrum in which the amine surface spectrum was subtracted from the monolayer spectrum, showed a small amount of C=O stretch remaining (Figure 7). This might be attributed to a residual amount of the carboxylic acids that are not hydrogen bonded to the APTES, or to occasional molecules that are sitting in alternative orientation (lying on the side or standing upside down). Even so, the major resonances are CO\(_2^-\) stretches, which suggest the predominant upright orientation for \( \mathbf{1} \). The monolayer spectrum of \( \mathbf{2} \) is essentially the same (Supporting Information Figure S-12 and 13).

Monolayers of both \( \mathbf{1} \) and \( \mathbf{2} \) are very stable; the UV–vis spectrum did not show significant change over several weeks under air or more than 15 h under argon at 300 °C. Compared with the monolayer of \( \text{C}_{60} \) pentabiphenyl derivative (\( \text{C}_{60}(\text{C}_6\text{H}_4\text{C}_6\text{H}_4=\text{COOH})_5\text{Me} \)) on gold,\(^{d4}\) the coverage 0.42 molecules/nm\(^2\) for the monolayer of \( \mathbf{1} \) and 0.50 molecules/nm\(^2\) for the monolayer of \( \mathbf{2} \) is quite reasonable (0.40 molecules/nm\(^2\) for pentabiphenyl derivative). It is interesting to note that the pentabiphenyl derivative stands upright on bare gold surface without any adhesion layer under in situ STM conditions. To explore the utility of these monolayers, we will show examples of both \( n \)-type and \( p \)-type transistors using the monolayers as a functionalized insulating layer.

First SAMs of \( \mathbf{1} \) and \( \mathbf{2} \) were tested to see their effects on \( n \)-type FETs made from \( \text{C}_{60} \). Au/Cr electrodes were deposited (5 nm Cr followed by 50 nm Au) through a shadow mask by thermal evaporation onto a silicon wafer that has a 300 nm oxide layer as an insulator, then the monolayer of either \( \mathbf{1} \) or \( \mathbf{2} \) was assembled on top of this substrate. The channel length was 10 \( \mu \)m and the electrode width was 115 \( \mu \)m. \( \text{C}_{60} \) was then thermally evaporated onto the substrate (1.5–1.7 Å/s at <10\(^{-6}\) Torr, \( \text{C}_{60} \) layer thickness: 50 nm). The measurement was carried out in a glovebox without exposing the device to air. The output of the resulting transistor is shown in Figure 8b. With a monolayer of \( \mathbf{1} \), the mobility was \( \mu = 0.02 \text{ cm}^2 \text{ V}^{-1} \text{ s}^{-1} \), which is quite typical for \( \text{C}_{60} \)
With a monolayer of 2 the mobility was increased to \( \mu = 0.04 \text{ cm}^2\text{ V}^{-1}\text{ s}^{-1} \), which is twice as high as with the monolayer of 1. The difference is attributable to the ferrocene moiety: since C\(_{60}\) is an electron acceptor and ferrocene is an electron donor, carrier generation is more efficient in the presence of ferrocene than in its absence. The threshold voltage was \(-34 \text{ V}\) in the case of 1 and \(-22 \text{ V}\) for 2. This is a large shift from the typical value, which is \(>0 \text{ V}\). An aligned dipole layer generated by the salt of amine and carboxylic acid at the interface of 1 (or 2) and APTES monolayer could be responsible for the shift of the threshold voltage.

Recently, we reported that the contorted hexabenzocoronene (HBC), 3, shows good performance in spuncoat OFETs. The effect of monolayers of 1 and 2 in the FETs using 3 was investigated. Beneficial intermolecular interactions can be expected in these pairings, not only because C\(_{60}\) is an electron acceptor and HBC is a donor but also because their shapes, a ball and a socket, respectively, are complementary (Figure 9).

The device was fabricated as follows. Au/Cr electrodes were evaporated (5 nm Cr followed by 50 nm Au) through a shadow mask onto the silicon wafer, which has 300 nm oxide layer as an insulator. The channel was 85 \(\mu\)m long and 2 mm wide. Then the solution of 3 was spuncoat onto the SAMs of 1 or 2. The transistor output is shown in Figure 10. When the measurement was carried out in the dark, two devices showed similar characteristics (dotted lines); however, when the measurement was carried out in the ambient light, we found an interesting change: the transistor incorporating 1 had higher current than the one with 2. The light–dark current ratio \((I_{D\text{light}}/I_{D\text{dark}})\) at \(V_{S\text{-D}} = -100 \text{ V}\) was 14 for the former and 3 for the latter. We measured a similar OFET that used an acetic acid layer instead of 1 (or 2). Although it had negligible current either with or without light, the light–dark current ratio at \(V_{S\text{-D}} = -100 \text{ V}\) was 2.5, which is similar to the FET with an electron acceptor and HBC is a donor but also because their shapes, a ball and a socket, respectively, are complementary (Figure 9).

The acetic acid layer was prepared using the same method as for the preparation of the monolayer of 1 and 2. The concentration of the acetic acid solution was five times higher than the solution of 1 and 2 to make the concentration of the “acid” (number of the \(-\text{COOH}\) group) same. We consider that the acetic acid makes a salt on APTES surface which prevents from evaporation.


(16) Acetic acid layer was prepared using the same method as for the preparation of the monolayer of 1 and 2. The concentration of the acetic acid solution was five times higher than the solution of 1 and 2 to make the concentration of the “acid” (number of the \(-\text{COOH}\) group) same. We consider that the acetic acid makes a salt on APTES surface which prevents from evaporation.

Figure 8. (a) Schematic illustration of an FET fabricated for C\(_{60}\) transistors. Fc: ferrocene. (b) Transistor output for C\(_{60}\) transistors with the monolayer of 1, 2. (c) Transconductance: The dotted lines are a fit of the linear portion of the data points. The source-drain voltage \(V_{S\text{-D}}\) was held at 80 V.

Figure 9. Structure of contorted hexabenzocoronene. (a) Front view. (b) Side view.

Figure 10. Transistor output of HBC 3 with different kinds of monolayer. Inset is the output for the transistors with acetic acid monolayer.
the monolayer of 2. Thus the behavior of the monolayer/ 
HBC devices can be explained by the photoinduced charge 
transfer between C_{60} moiety of the monolayer and the 
HBC.\textsuperscript{8h,17} The lower current with the monolayer of 2 could 
be attributed to the electron-donating ferrocene. Charge 
transfer from HBC might be suppressed by ferrocene which 
leads to ineffective channel formation by light.

**Conclusion**

We have demonstrated the formation of uniform mono-
layers of the compounds 1 and 2 on silicon oxide surfaces 
with a straightforward method that involves dipping the 
amino-terminated surface into the solution of the C_{60} 
derivatives. This does not require any covalent modification 
of C_{60} on the surface, which could potentially result in a 
nonuniform modification of the C_{60} molecules resulting in 
a surface of a nonuniform electronic structure. The mono-
layer could be used for the surface modification of the 
insulating layer of OFETs. When C_{60} was used as a 
semiconducting layer in an OFET, the mobility when 1 
was used was 0.02 cm\(^2\) V\(^{-1}\) s\(^{-1}\). This value doubles in the 
presence of the monolayer of 2, indicating the efficient 
channel formation by electron donating ferrocene moiety.

A more surprising fact is the generation of photocurrent in 
the presence of contorted HBC, 3. Both the donor—acceptor 
interaction and the geometrical ball—socket interaction 
apparently play important roles in the photocurrent 
generation.\textsuperscript{15}

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**Supporting Information Available:** UV–vis spectra of the 
compound 1 and 2 both for the solution and the monolayer, 
AFM images for the monolayer of 1 and 2, model parameters 
for X-ray reflectivity, survey spectra of XPS analysis of the 
monolayer of 1 and 2, the high resolution scan for N 1s region of 
the monolayer of 2, IR spectrum of the compound 2 both for 
bulk and the monolayer, and details of the OFETs properties. 
This material is available free of charge via the Internet at http:// 
pubs.acs.org.

\textsuperscript{(17)} Yamamoto, Y.; Zhang, G.; Jin, W.; Fukushima, T.; Ishii, N.; 
Saeki, A.; Seki, S.; Tagawa, S.; Minari, T.; Tsukagoshi, K.; Aida, 